

Figure 1. XPS depth profile of the PEALD nickel film deposited at 150°C.

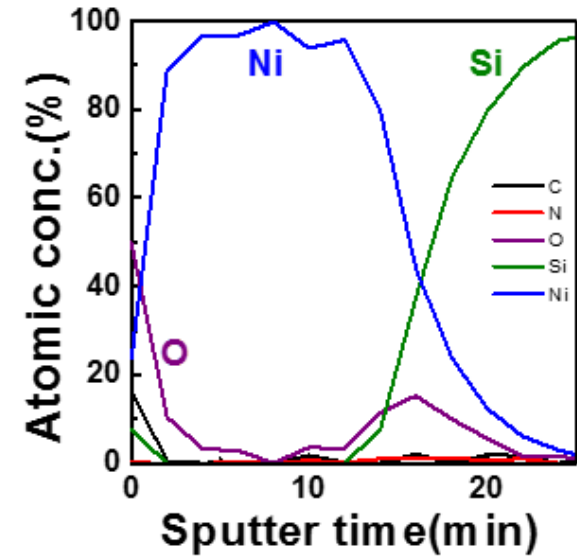


Figure 2. XPS depth profile of the PEALD nickel film after annealing in H₂ at 400°C.